

ORBITING INDEXABLE BELT POLISHING STATION FOR CHEMICAL MECHANICAL POLISHING

DESCRIPTION

Cross Reference to Related Applications

[Para 1] This is a divisional application of and claims priority to U.S. Non-Provisional Application No. 09/705,307, entitled "Orbiting Indexable Belt Polishing Station for Chemical Mechanical Polishing", filed on November 3, 2000, which application is incorporated herein by reference. *pat. no. missing*

Field of Invention

[Para 2] The present invention relates generally to systems for polishing or planarizing workpieces such as semiconductor wafers. More particularly, it relates to an improved apparatus and method for planarizing a wafer using an orbiting indexable fixed-abrasive web.